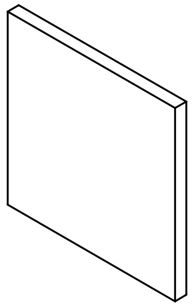
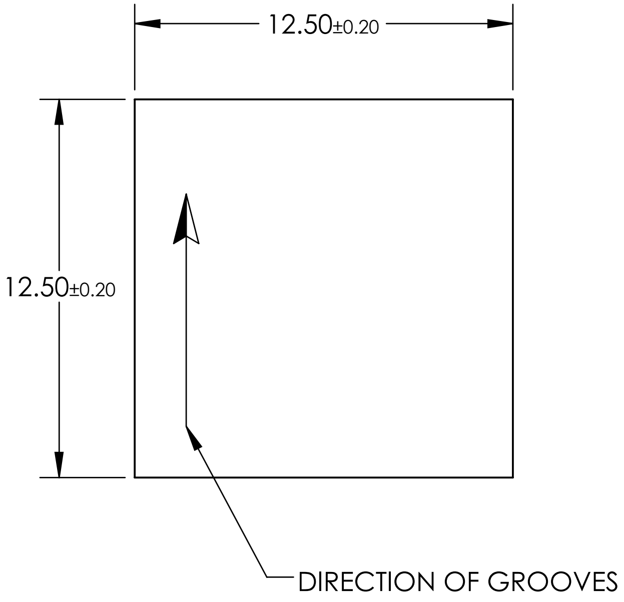
NOTES:
1. SUBSTRATE MATERIAL:
Single Crystal Silicon

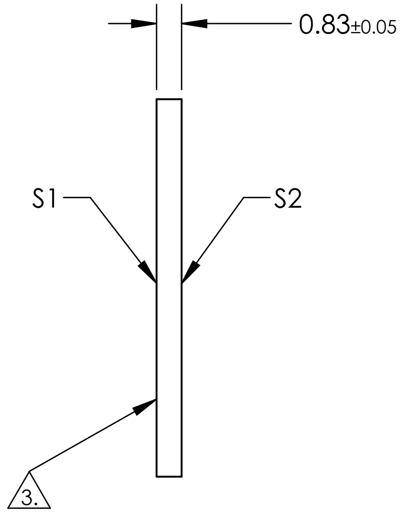
2. PERIOD: 139 ±6.95nm
LINE WIDTH: 50 ±5nm
GROOVE DEPTH: 50 ±7.5nm

3. RIE TREATED SURFACE

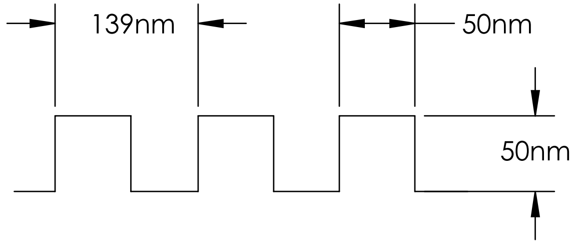
4. RoHS COMPLIANT







CROSS SECTION VIEW OF GRATING SURFACE



FOR INFORMATION ONLY:
DO NOT MANUFACTURE
PARTS TO THIS DRAWING

SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE
DIMENSIONS ARE FOR REFERENCE ONLY

	S1	S2
SHAPE	PLANO	PLANO
SURFACE QUALITY	60-40 (within CA)	FINE GRIND
CLEAR APERTURE	11.50 x 11.50	N/A
BEVEL	PROTECTED AS NEEDED	PROTECTED AS NEEDED

Edmund Optics®

THIRD ANGLE PROJECTION		TITLE	II-VI LightSmyth™ 139nm, 50nm Groove Depth, 12.5mm Sq. Linear Silicon Nanostamp	
ALL DIMS IN	mm	DWG NO	16857	SHEET 1 OF 1